

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)					Docket No. 8235/ETCH/DRIE/JB1		Serial No. 10/674,700	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant Ye, et al.		Confirmation No.:	
(Use several sheets if necessary)					Filing Date 09/29/2003		Group	
Examiner								
U.S. Patent Documents								
*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate	
L.T.M.-E	A1	6,514,672	02/04/2003	Young et al.	430	314		
L.T.M.-E	A2	2001/0046632	11/29/2001	Young et al.	430	5	06/11/2001	
	A3							
	A4							
	A5							
	A6							
	A7							
	A8							
	A9							
	A10							
	A11							
	A12							
Foreign Patent Documents								
*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1						<input type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>
	B3						<input type="checkbox"/>	<input type="checkbox"/>
	B4						<input type="checkbox"/>	<input type="checkbox"/>
OTHER ART								
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.						
L.T.M.-E	C1	Mahorowala, et al., "Transfer Etching of Bilayer Resists in Oxygen-based Plasmas," Journal of Vacuum Science & Technology A: Vacuum, Surfaces, and Films 18 (4), 1411-1419 (July 2000).						
	C2							
	C3							
Examiner <i>Lynette T. Umeg-Ewuruni</i>					Date Considered <i>9/29/2005</i>			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								